

**Amendments to the Specification**

Please replace the paragraph extending from page 7, line 16-26, with the following amended paragraph:

As mentioned above, in the embodiment of FIGS. 3A-4, the polarization field has a magnitude ( $\xi_p$ ) that is sufficient to align conduction band states near  $E_F$  at first heterointerface 18 with valence band states near  $E_F$  at second heterointerface 20. That is,  $\xi_p$  has a value that is on the order of  $(E_{c,1}-E_{v,2})/(q \cdot D)$ , where  $E_{c,1}$  is a relative conduction band energy at first heterointerface 18,  $E_{v,2}$  is a relative valence band energy at second heterointerface 20,  $q$  is a unit carrier charge, and  $D$  is the thickness of the intermediate semiconductor layer 16. In particular, in this embodiment,  $\xi_p$  has a value that is greater than  $(E_{c,1}-E_{v,2})/(q \cdot D) - \xi_d$ , where  $\xi_d$  is the value of the dopant-induced drift field through the intermediate semiconductor layer as shown in FIG. 3A. Consequently, although the intermediate semiconductor layer thickness ( $D$ ) should be thin enough to enable charge carriers to tunnel therethrough, it should not be thinner than  $(E_{c,1}-E_{v,2})/(q \cdot (\xi_p + \xi_d))$ .